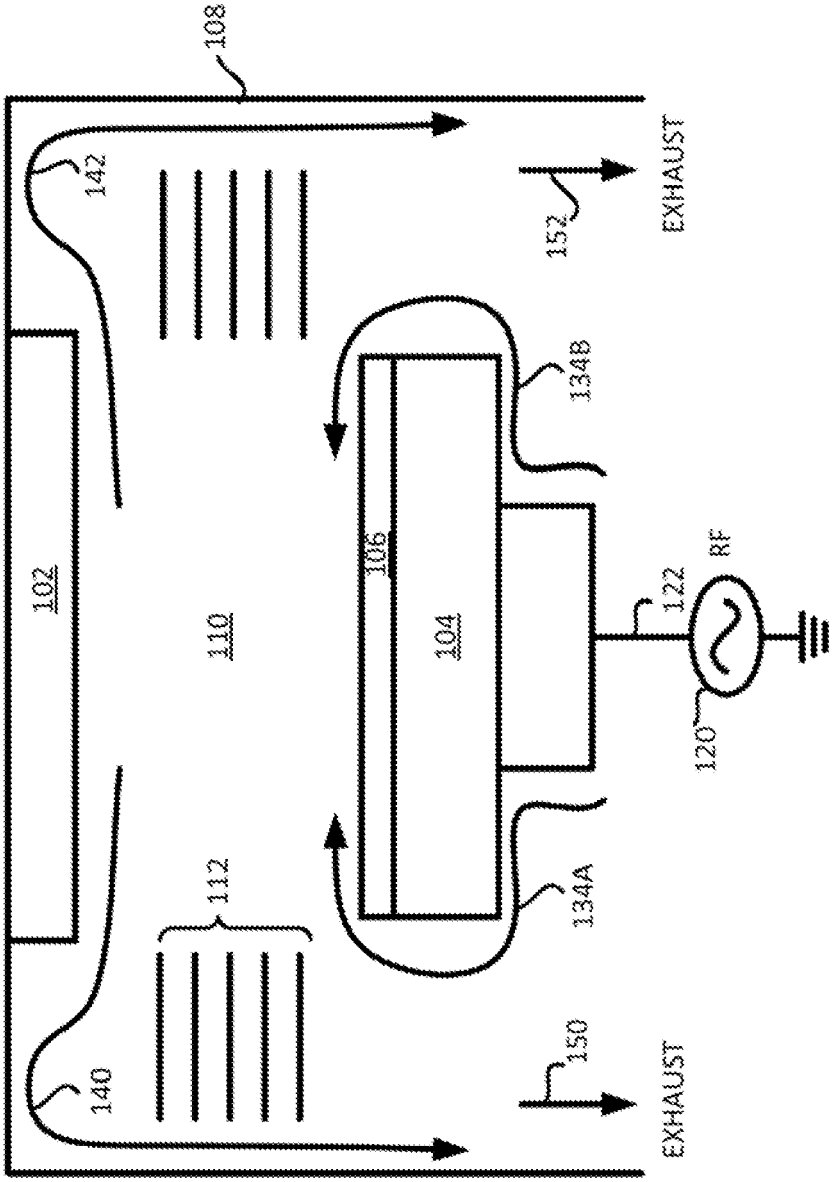


FIG. 1
(PRIOR ART)

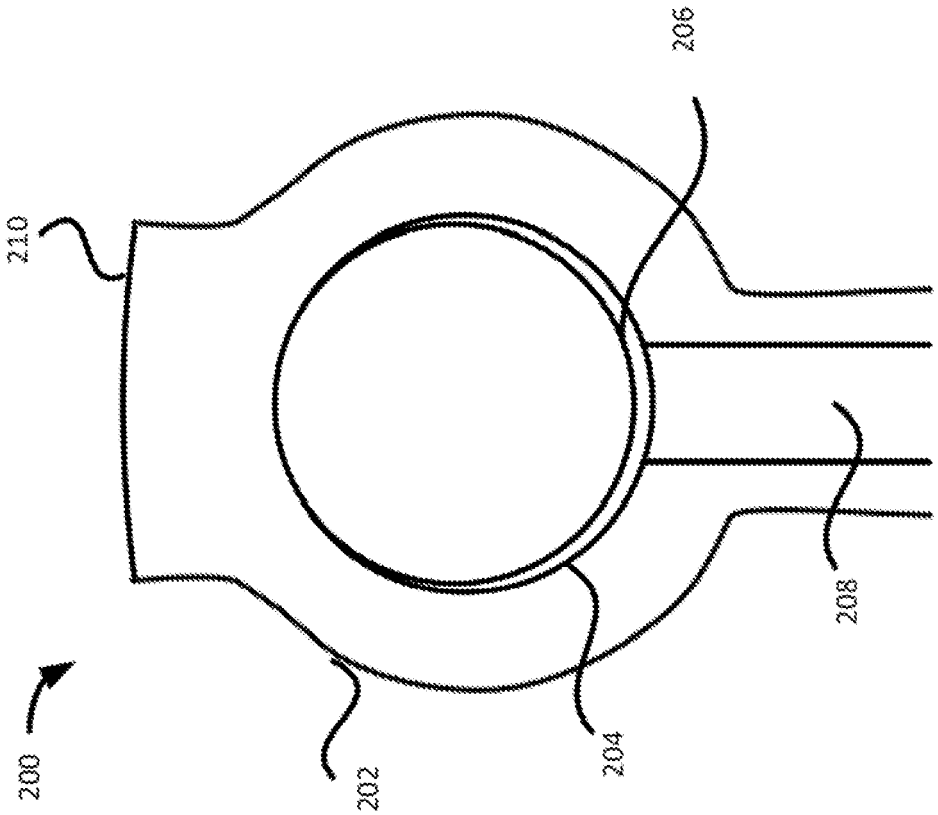


FIG. 2A
(PRIOR ART)

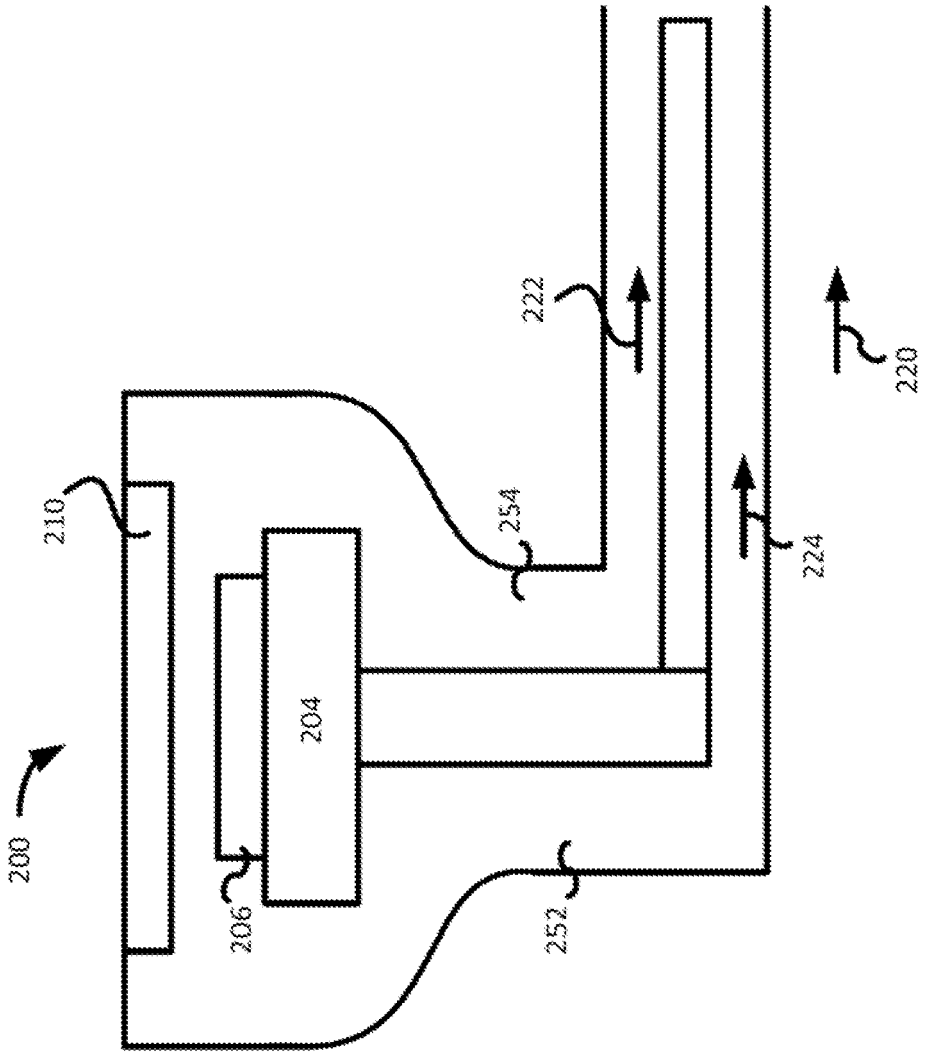


FIG. 2B
(PRIOR ART)

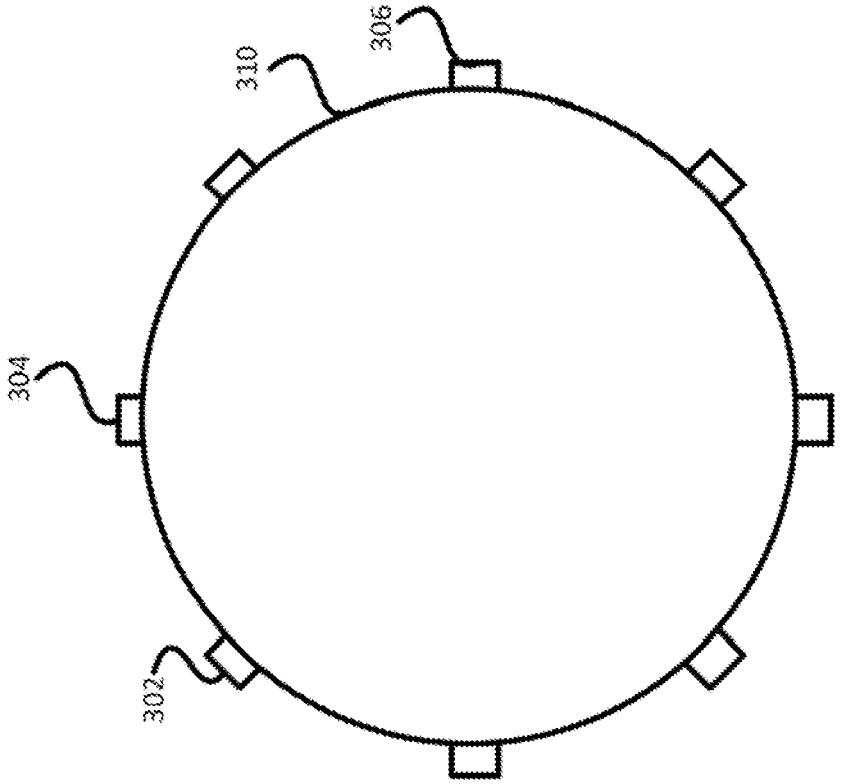


FIG. 3A

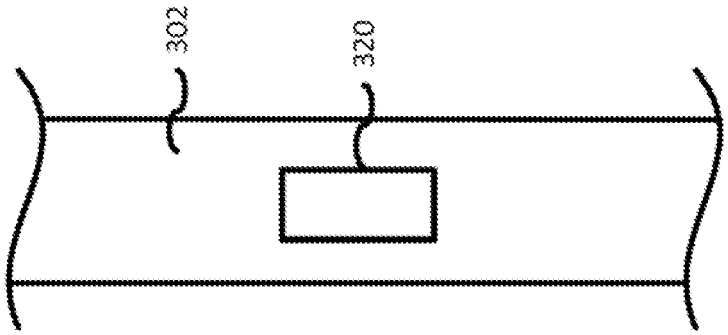


FIG. 3B

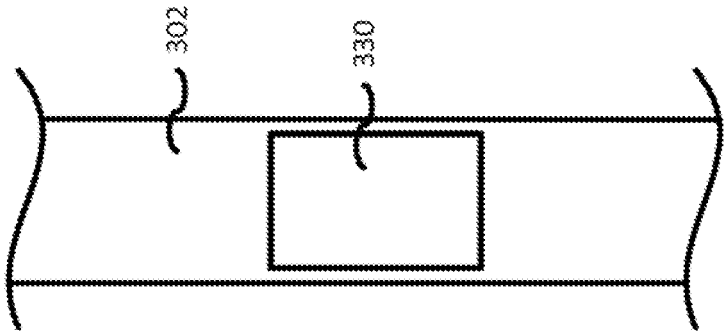


FIG. 3C

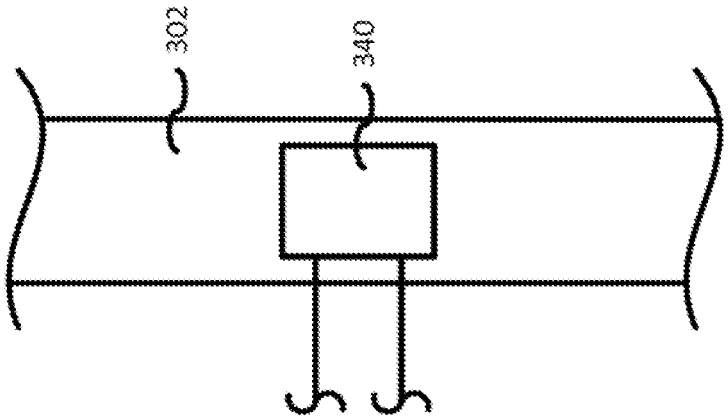


FIG. 3D

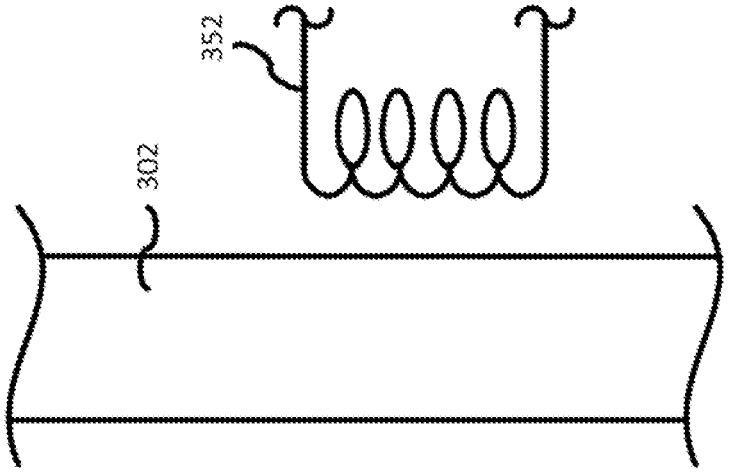


FIG. 3E

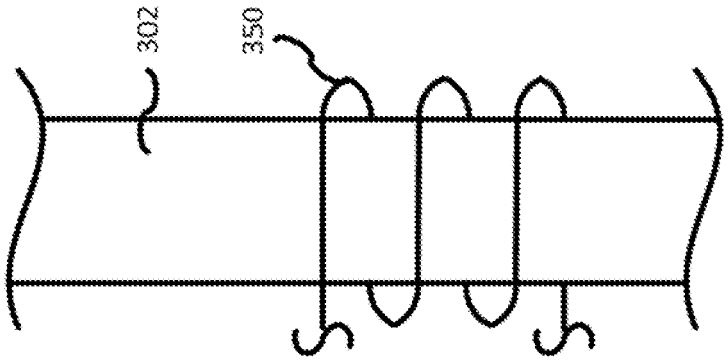


FIG. 3F

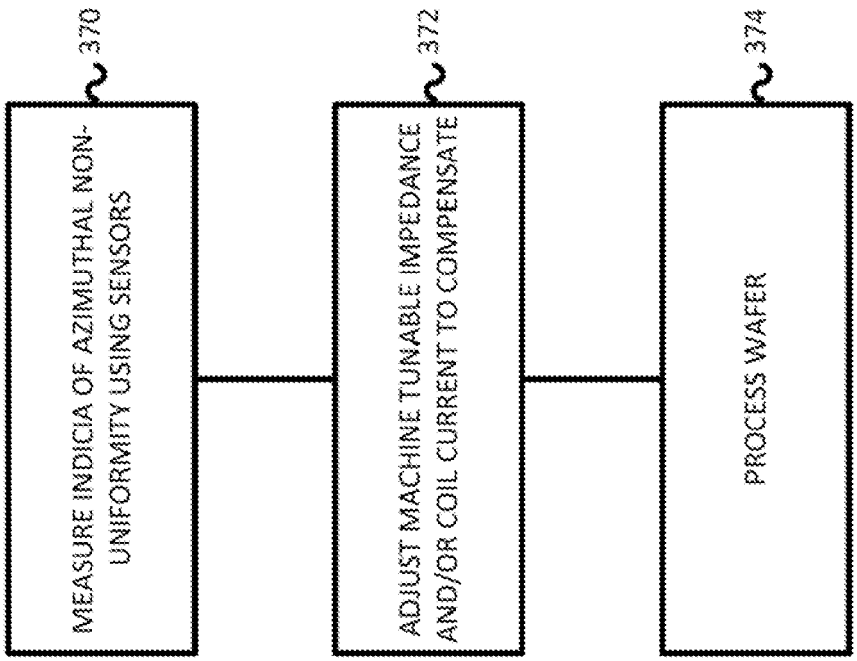

370
MEASURE INDICIA OF AZIMUTHAL NON-UNIFORMITY USING SENSORS
372
ADJUST MACHINE TUNABLE IMPEDANCE AND/OR COIL CURRENT TO COMPENSATE
374
PROCESS WAFER

FIG. 3G

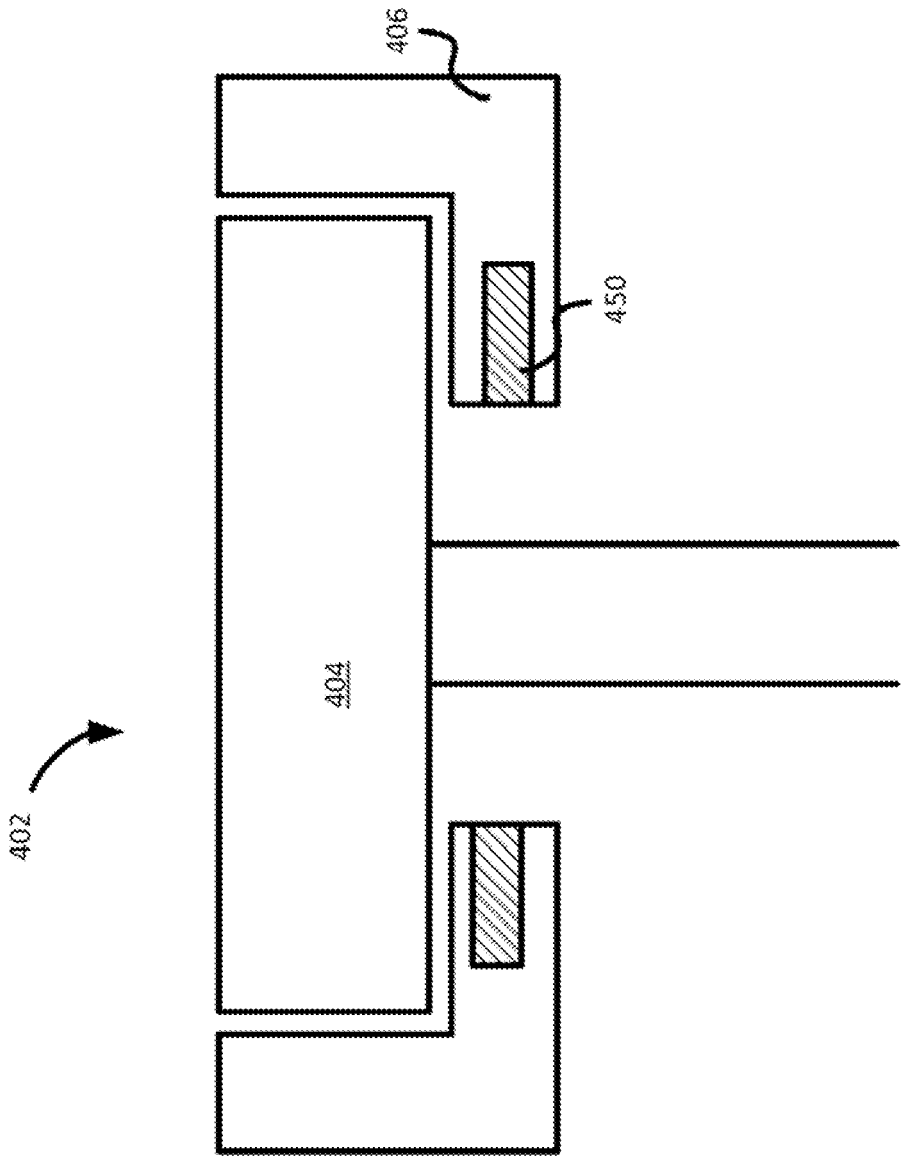


FIG. 4A

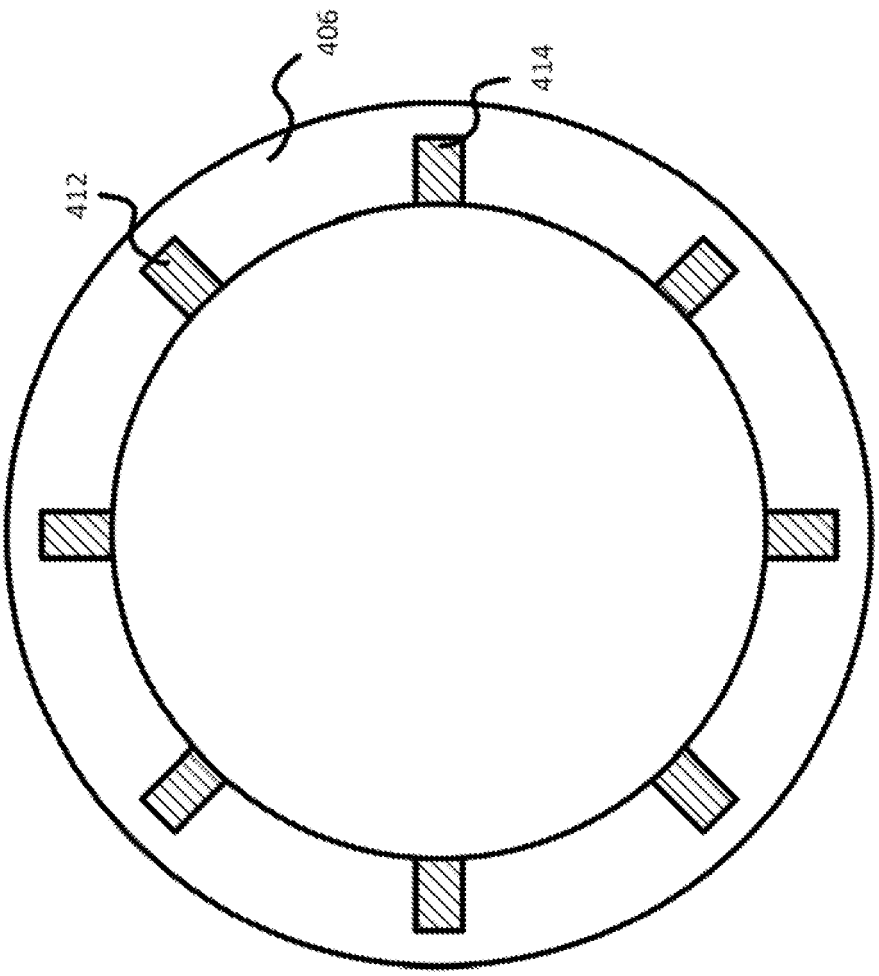


FIG.4B

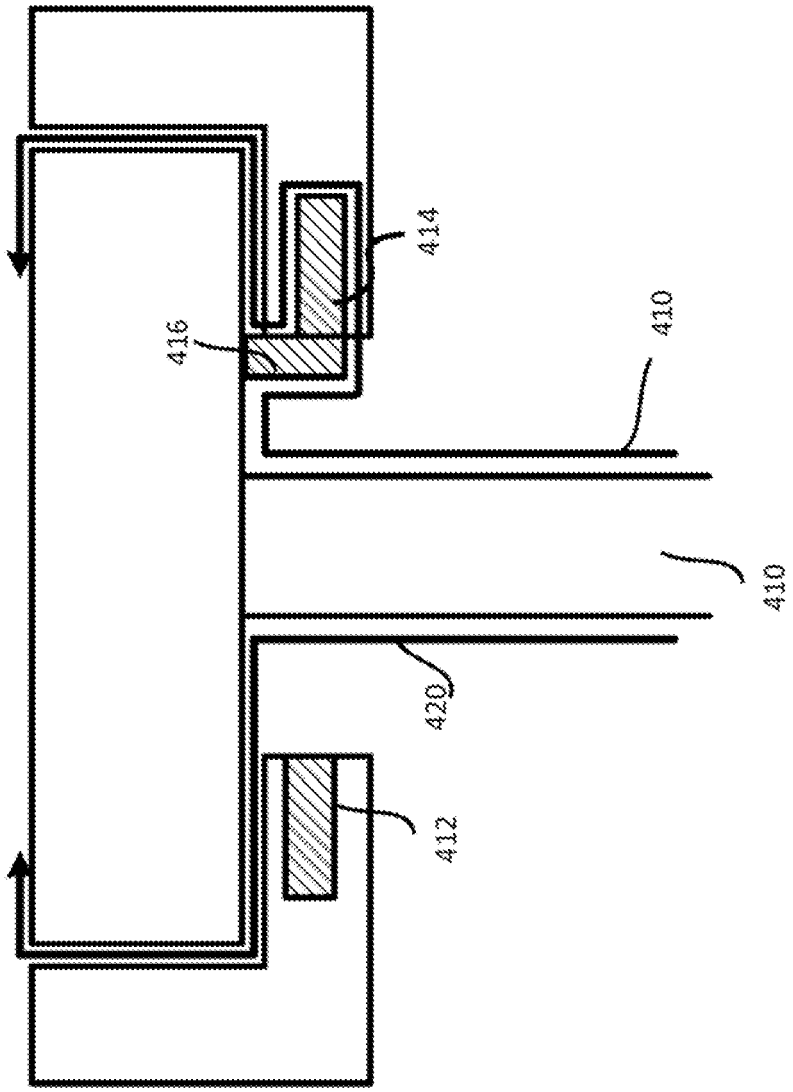


FIG. 4C

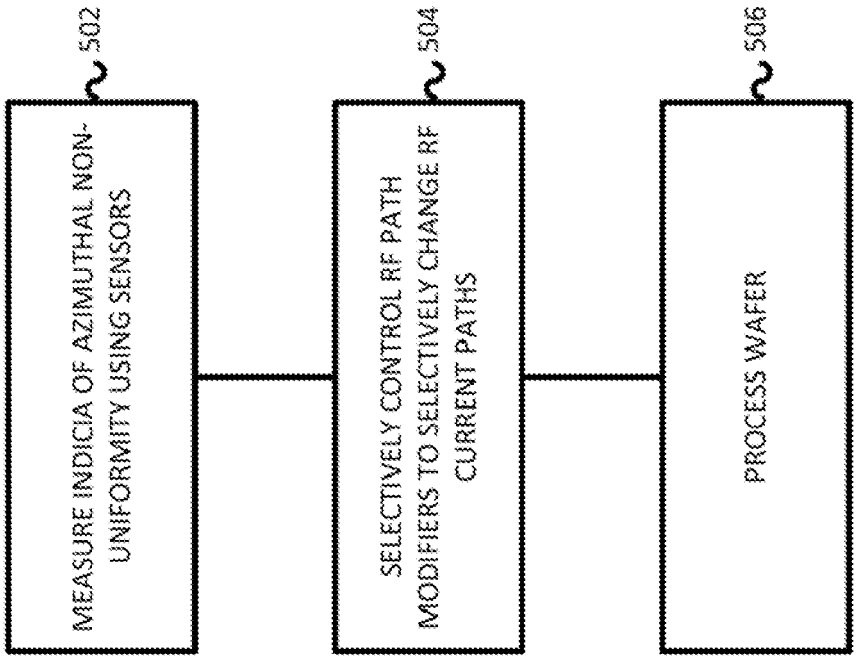

502
MEASURE INDICIA OF AZIMUTHAL NON-UNIFORMITY USING SENSORS
504
SELECTIVELY CONTROL RF PATH MODIFIERS TO SELECTIVELY CHANGE RF CURRENT PATHS
506
PROCESS WAFER

FIG. 5

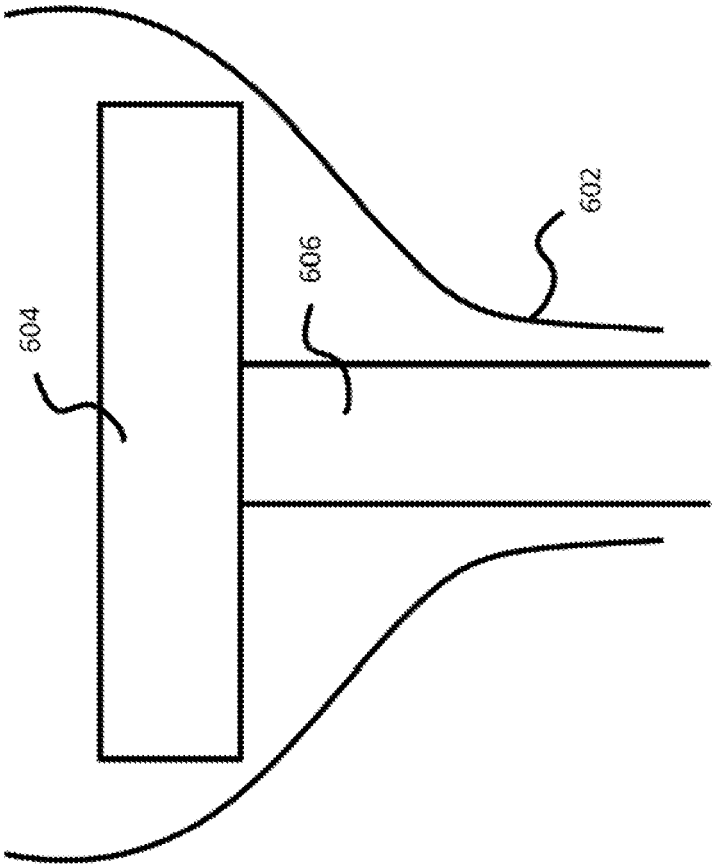


FIG. 6

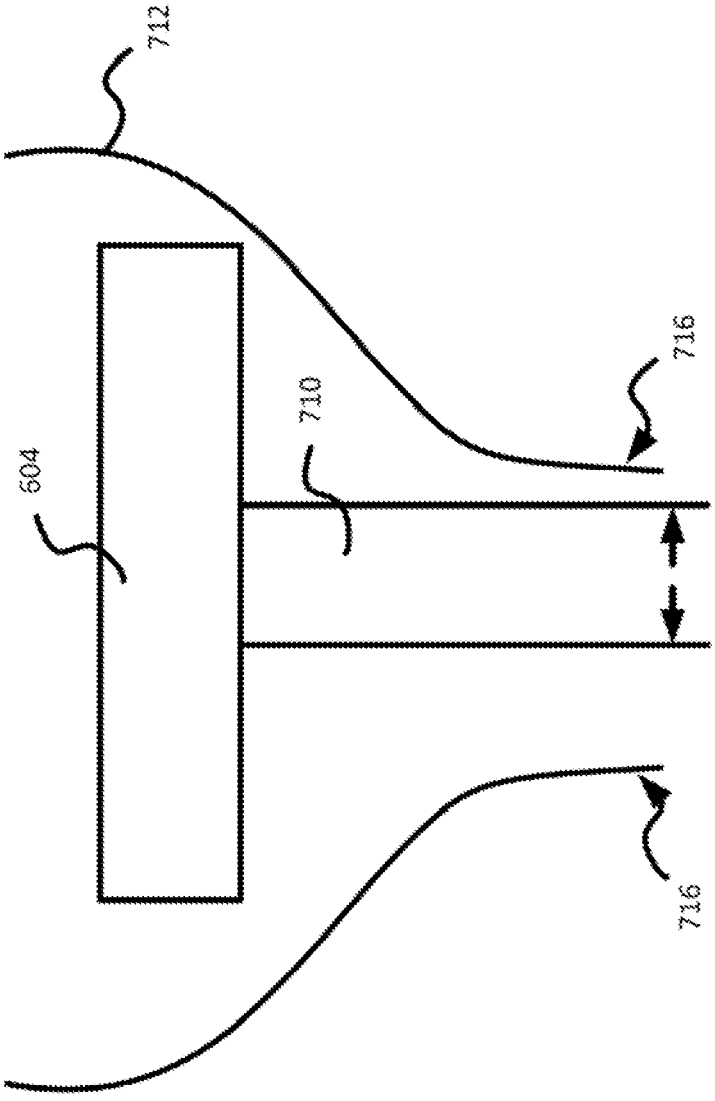


FIG. 7

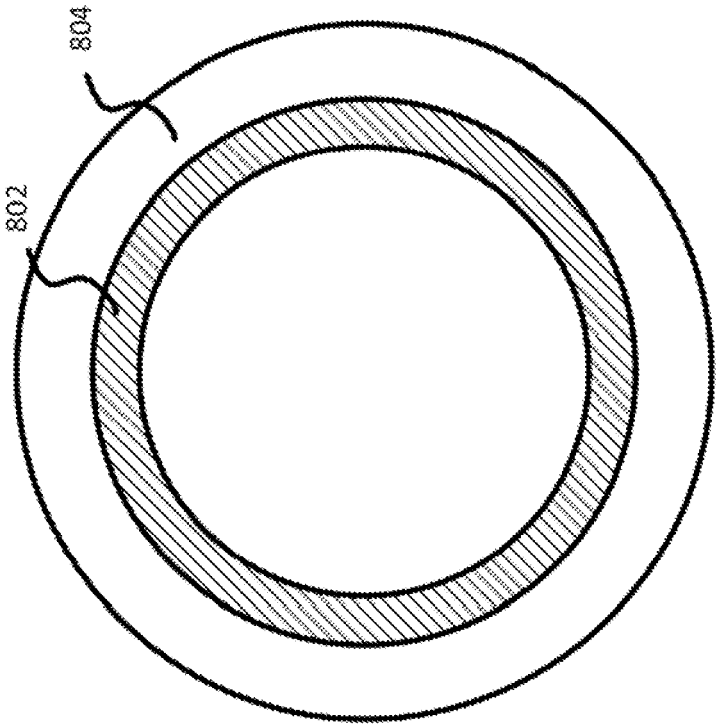


FIG. 8

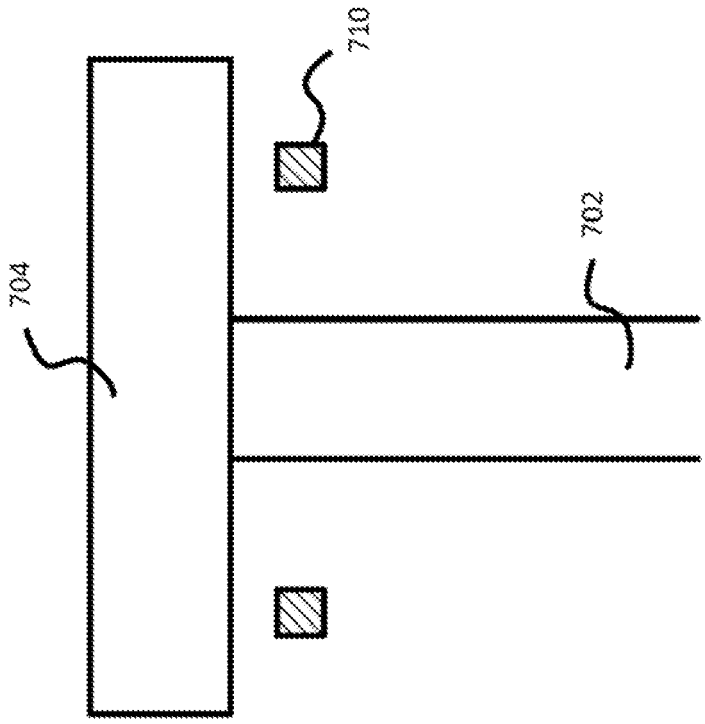


FIG. 9

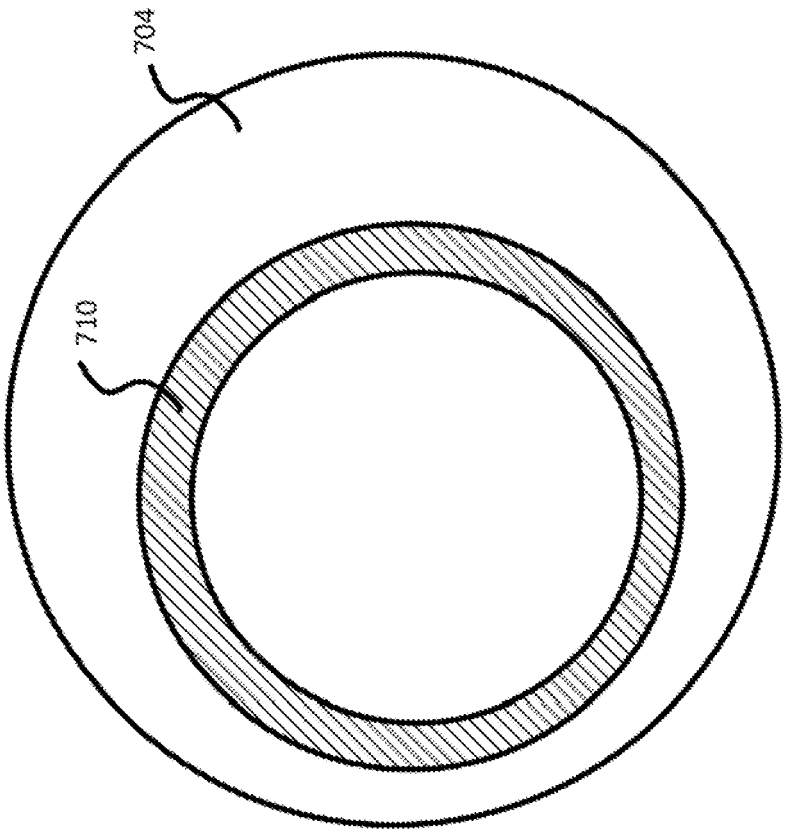


FIG. 10

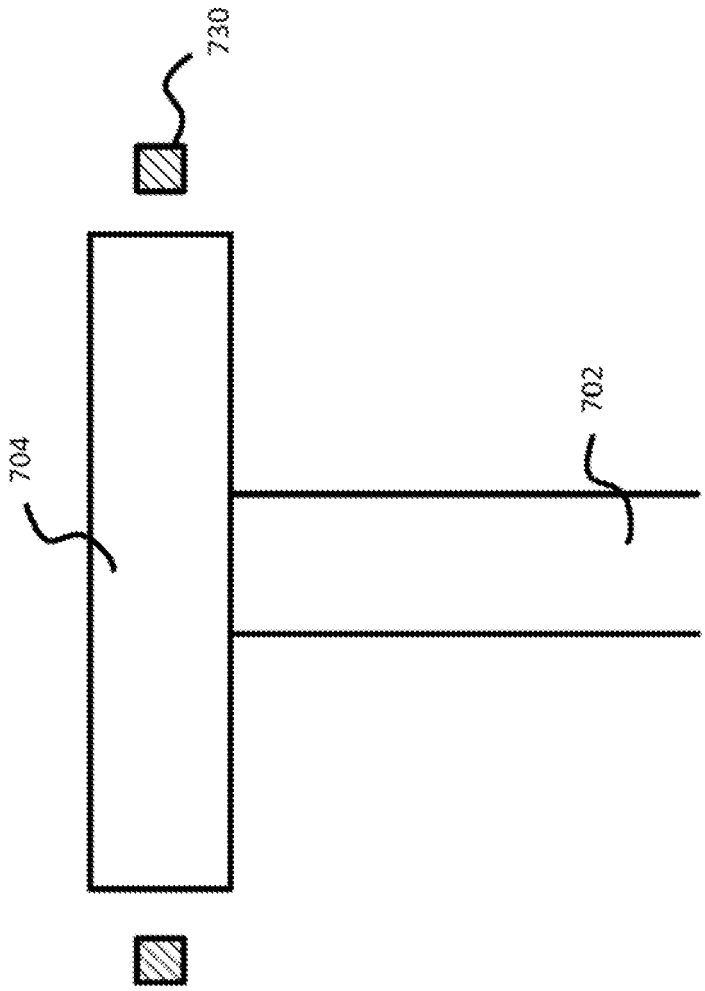


FIG.11

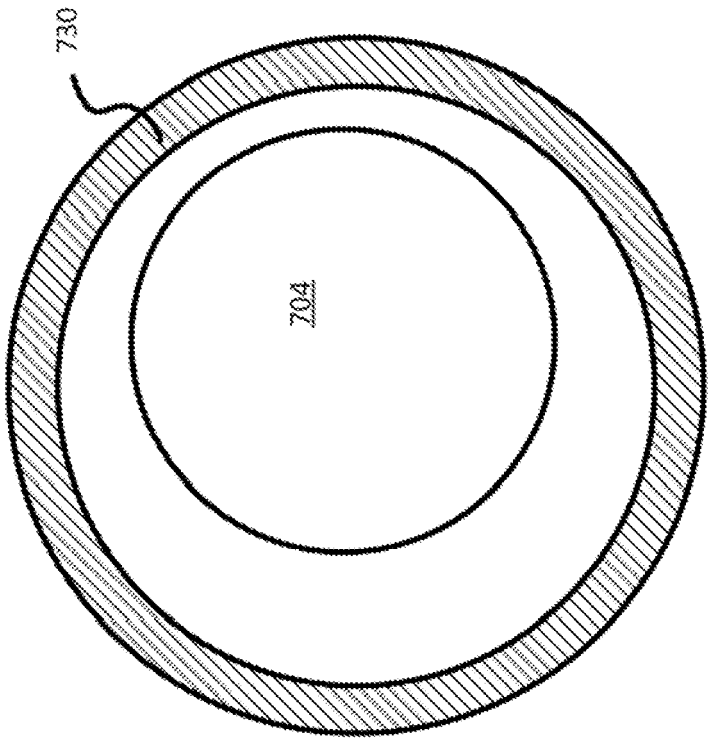


FIG. 12

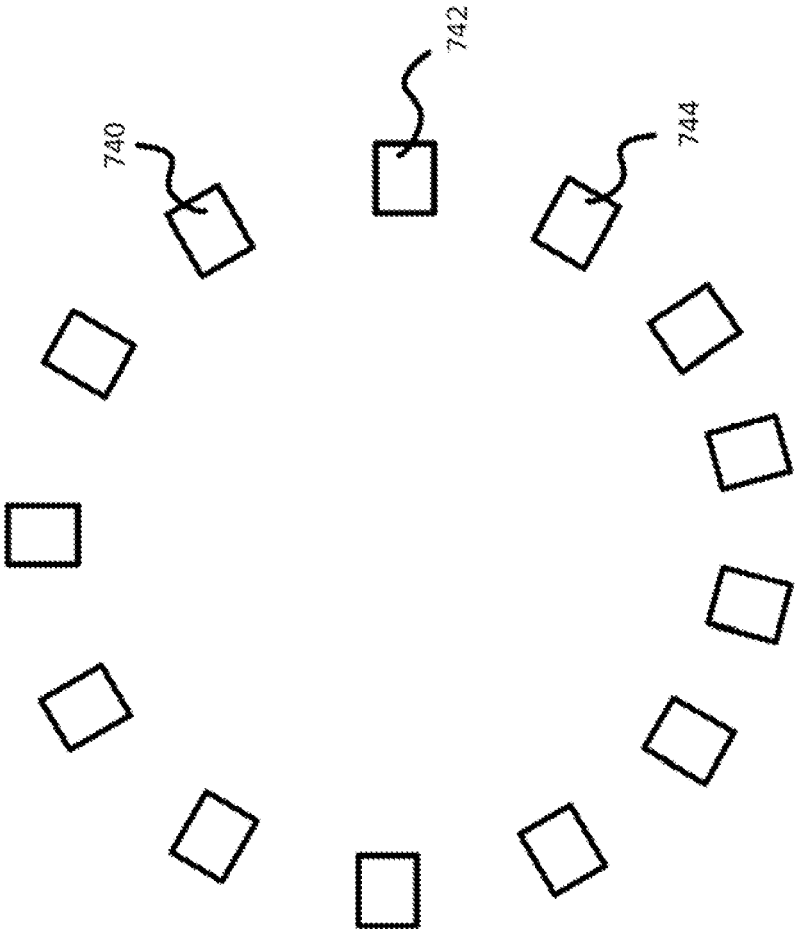


FIG.13